



*STW*

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q77049

Kesahiro KOIKE, et al.

Appln. No.: 10/642,657

Group Art Unit: 1756

Confirmation No.: 3050

Examiner: John S. Ruggles

Filed: August 19, 2003

For: METHOD OF PRODUCING A GLASS SUBSTRATE FOR A MASK BLANK, METHOD OF PRODUCING A MASK BLANK, METHOD OF PRODUCING A TRANSFER MASK, METHOD OF PRODUCING A SEMICONDUCTOR DEVICE, GLASS SUBSTRATE FOR A MASK BLANK, MASK BLANK, AND TRANSFER MASK

**RESPONSE TO RESTRICTION REQUIREMENT**

**MAIL STOP AMENDMENT**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated May 2, 2005, please consider the remarks as submitted herewith on the accompanying pages.